

## ABSTRACT

A pattern enlarged from a transfer pattern is divided into patterns ( $P_i$ ) of a plurality of master reticles ( $R_i$ ). Images of the patterns ( $P_i$ ) of the plurality of master reticles ( $R_i$ ) reduced by a projection optical system are successively projected and exposed on the surface of a blank (mask substrate) while stitching. Marks ( $M1$ ,  $M2$ ) indicating identification information for identifying a master reticle from another master reticle, transfer positions, etc. are formed on the master reticles ( $R_i$ ). These marks ( $M1$ ,  $M2$ ) are detected before the exposure and exposure is performed in accordance with the information on the transfer position etc. shown by the marks ( $M1$ ,  $M2$ ) or reticle information (exposure conditions, various correction values, etc.) relating to the master reticles stored and held in advance corresponding to the identification information. The number of work steps when producing a working reticle using the plurality of master reticles is reduced and occurrence of work errors can be prevented.